

Title (en)

LITHOGRAPHIC APPARATUS WITH THERMAL CONDITIONING SYSTEM FOR CONDITIONING THE WAFER

Title (de)

LITHOGRAFISCHE VORRICHTUNG MIT THERMISCHEM KONDITIONIERUNGSSYSTEM ZUR KONDITIONIERUNG EINES WAFERS

Title (fr)

APPAREIL LITHOGRAPHIQUE DOTÉ D'UN SYSTÈME DE CONDITIONNEMENT THERMIQUE POUR CONDITIONNER LA TRANCHE

Publication

**EP 3899663 A1 20211027 (EN)**

Application

**EP 19809088 A 20191128**

Priority

- EP 18213862 A 20181219
- EP 2019082878 W 20191128

Abstract (en)

[origin: WO2020126389A1] A lithographic apparatus receives radiation for imaging a pattern via projection optics onto a plurality of target areas on a substrate. Each target area receives a heat load through absorption of the radiation during imaging. The apparatus has thermal conditioning system to maintain the substrate at a spatially uniform, constant first temperature during the imaging. The thermal conditioning system has a heat sink operative to extract heat from the substrate; and a first heater system that supplies during the imaging, a first additional heat load to a part of the substrate. This part is the complement of the specific target area onto which the pattern is being imaged. The first additional heat load per unit area equals or exceeds a magnitude of the heat load per unit area.

IPC 8 full level

**G03F 7/20** (2006.01)

CPC (source: EP KR)

**G03F 7/7005** (2013.01 - EP KR); **G03F 7/70783** (2013.01 - EP KR); **G03F 7/70875** (2013.01 - EP KR)

Citation (search report)

See references of WO 2020126389A1

Designated contracting state (EPC)

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Designated extension state (EPC)

BA ME

DOCDB simple family (publication)

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DOCDB simple family (application)

**EP 2019082878 W 20191128**; CN 201980089412 A 20191128; EP 19809088 A 20191128; KR 20217022778 A 20191128; NL 2024322 A 20191128; TW 108146407 A 20191218